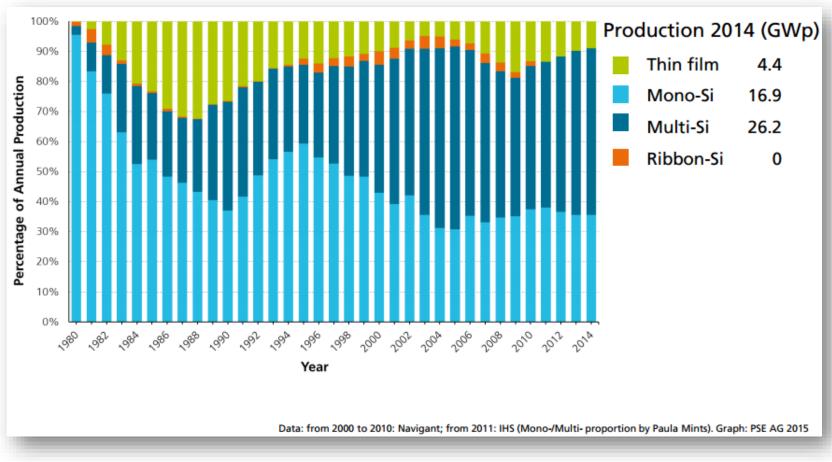
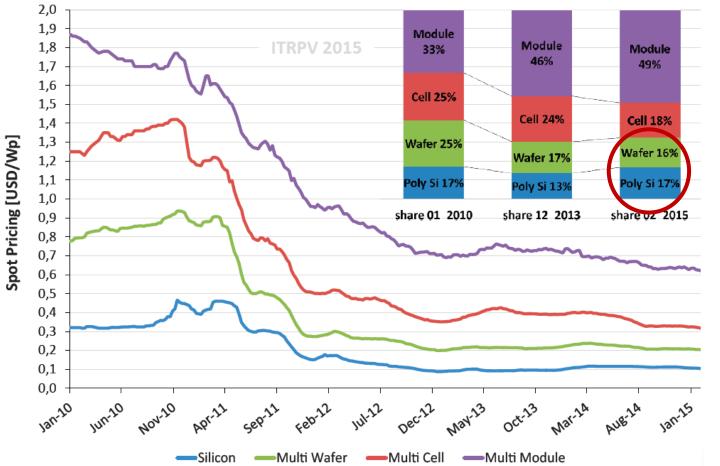
### Thin epitaxial silicon foils using porous-siliconbased lift-off for photovoltaic application

Ivan Gordon imec ASPIRE INVENT **ACHIEVE** 

# Crystalline silicon still dominates the photovoltaic market with a market share above 90%

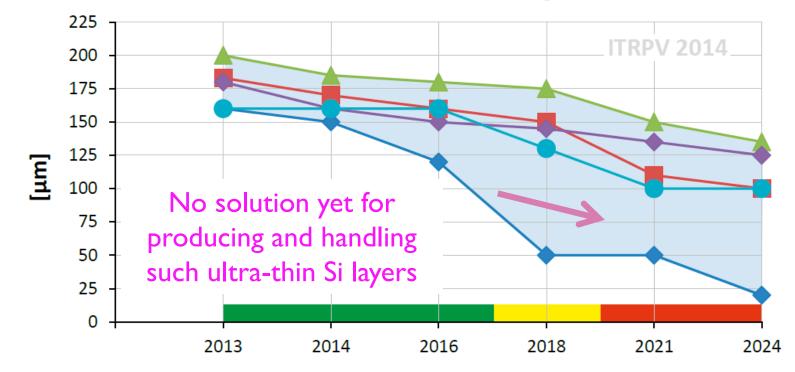


## The cost of the silicon material constitutes 33% of the total Silicon PV module cost



http://www.itrpv.net/

# By reducing the silicon wafer thickness, the cost of Silicon PV modules can be decreased substantially

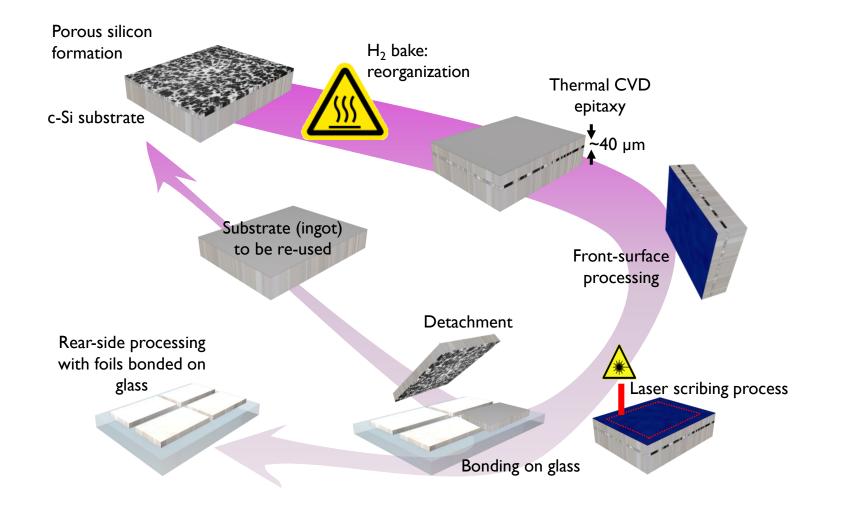


- ---- Minimum wafer thickness
- ----- Maximum wafer thickness
- Limit of cell thickness in current module technology
- --- Limit of cell thickness in alternative module technology

http://www.itrpv.net/

ime

#### Imec's approach is based on epitaxial silicon foils



#### Outline

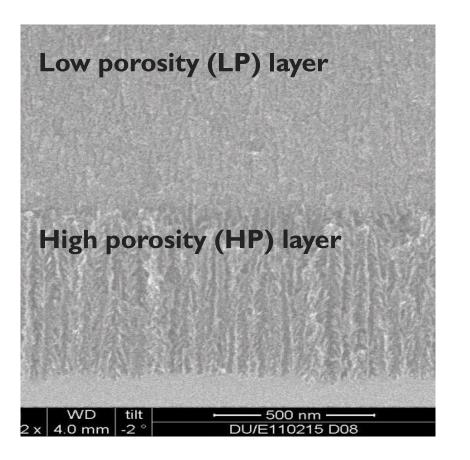
• Epitaxial foil development

• Solar cell development

#### $\circ$ Conclusions

### **Epitaxial foil development**

# Porous silicon serves as template for epitaxy and as detachment layer

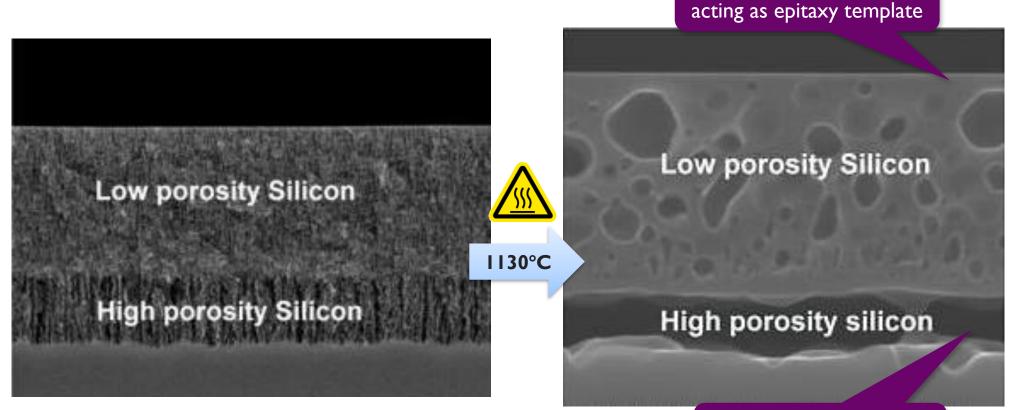


Electrochemical etching:

#### a **Low Porosity layer** (~30%) → needed for epitaxy

a **High Porosity layer** (~60%) → needed for detachment

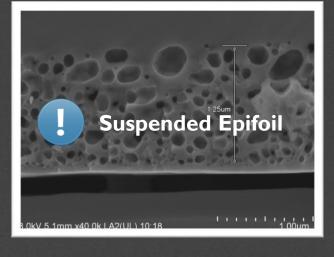
### Porous silicon serves as template for epitaxy and as detachment layer



**As-etched** 

Continuous void acting as separation layer

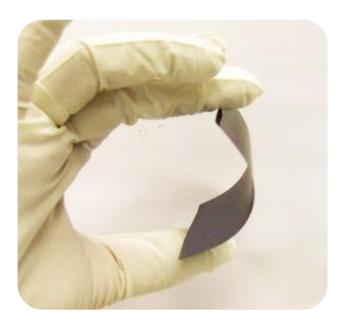
#### **Epifoil** – 40 µm, n-type



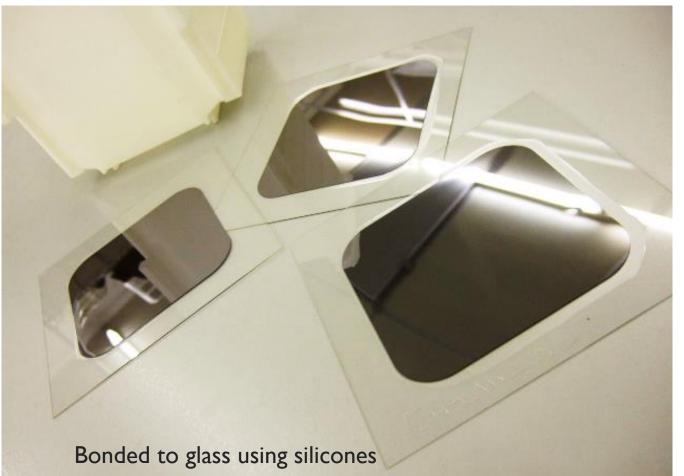
High-porosity layer – 300 nm

Parent substrate – 725 µm

### The foils can be detached from the parent substrate after epitaxial growth



Freestanding



## We use the minority carrier lifetime as measure for the material quality of the epitaxial foils

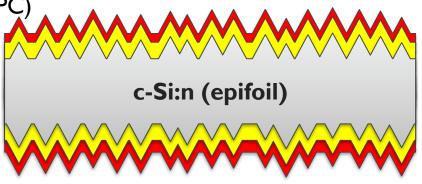
#### The quality of the epifoil material depends on:

- The quality of the porous Si template for epitaxy
- The epitaxial deposition process itself
- The detachment process (quality of separation layer)

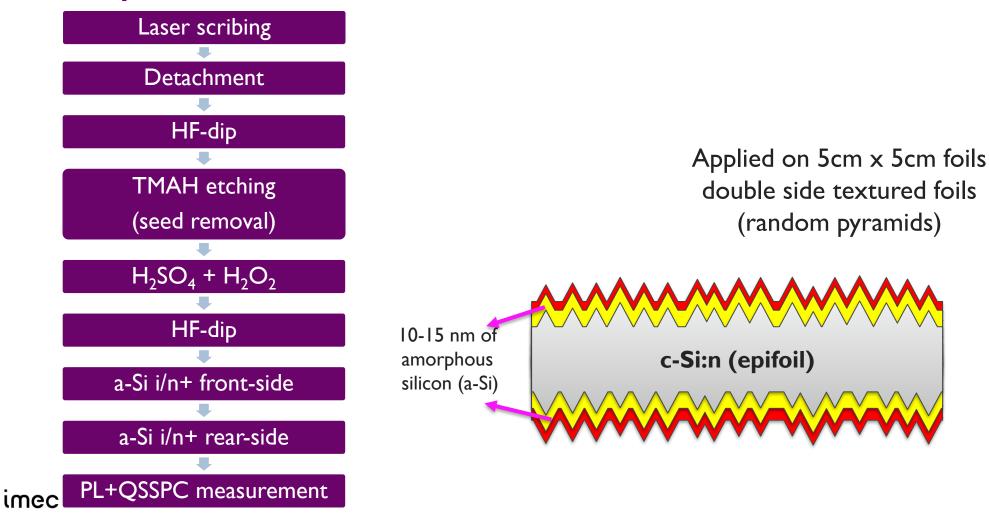
#### Lifetime measurements:

- Quasi Steady State PhotoConductance (QSSPC)
- Photolumicescence mapping (PL)

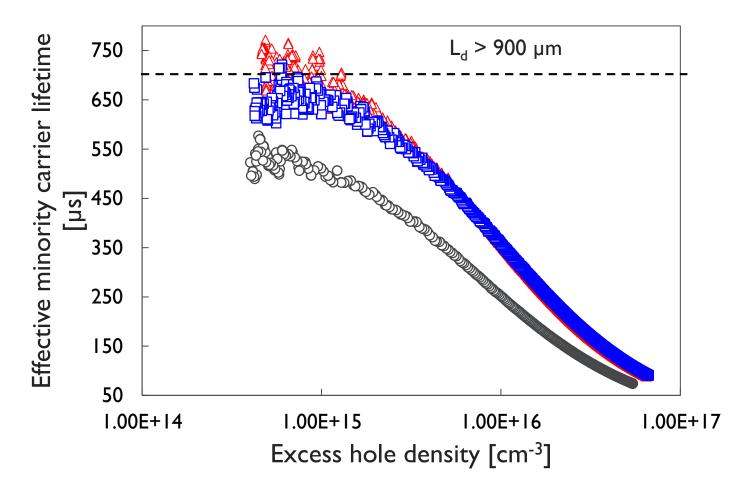
Applied on 5cm x 5cm foils double side textured foils (random pyramids)



## We use the minority carrier lifetime as measure for the material quality of the epitaxial foils

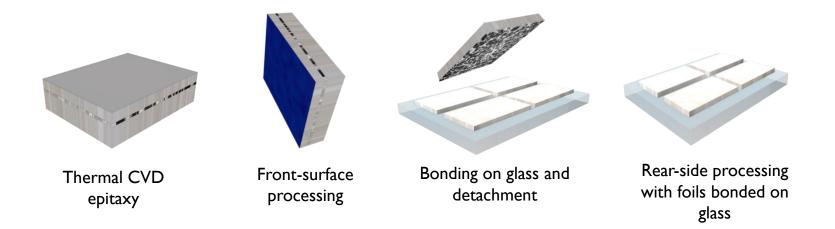


### High lifetimes have been obtained corresponding to bulk diffusion lengths of more than 25 times the layer thickness

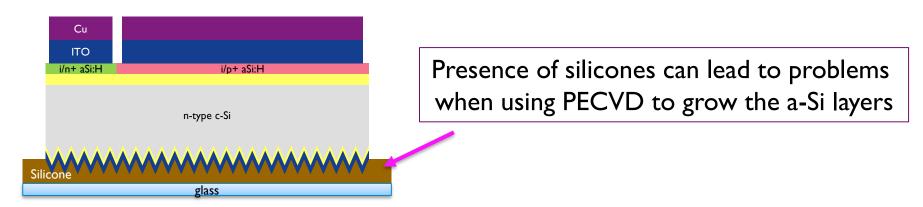


### Solar cell development

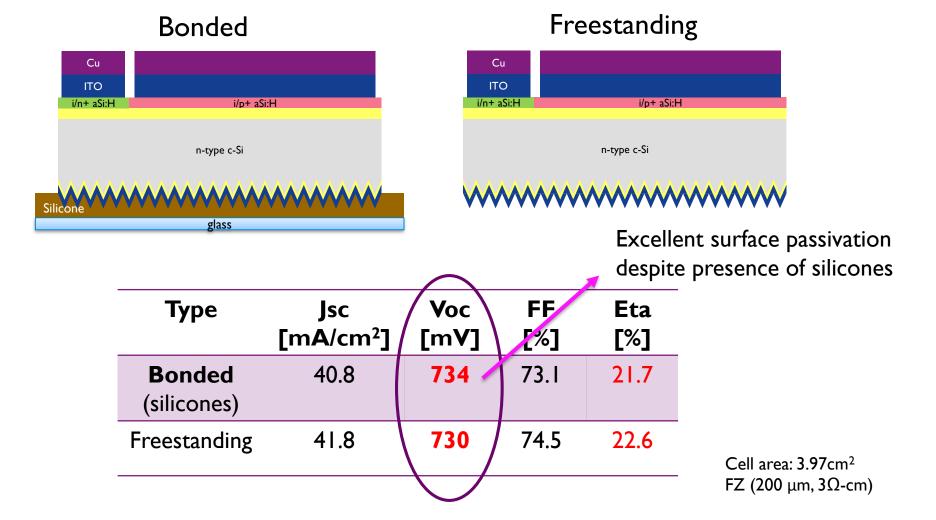
#### From epitaxial silicon foils to devices on glass



Targeted cell structure based on a-Si heterojunction and back contacts (SHJ-IBC)

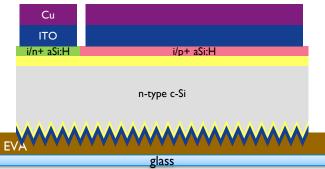


#### An SHJ-IBC cell process compatible with presence of silicones was developed successfully on Fz wafers of regular thickness



#### The SHJ-IBC cell process was also demonstrated on ultra-thin silicon Fz wafers

In this experiment, the bonding was done by EVA instead of silicones

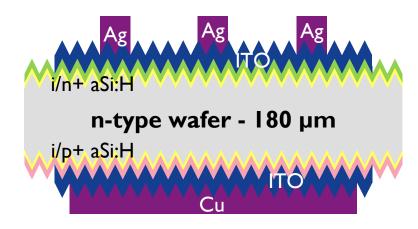


Starting thickness [um]	Jsc [m <b>A</b> /cm²]	Voc [mV]	FF [%]	Eta [%]
190	39.9	724	71.6	20.7
56	38.5	737	69.2	19.6

Cell area: 3.97cm<sup>2</sup> FZ wafers of various thickness

Slight decrease in efficiency for thin cells due to lower Jsc and FF

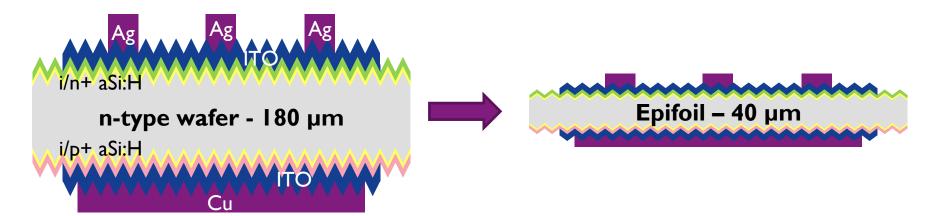
To test the quality of our epitaxial foils at device level we developed a simple freestanding cell process



Туре	Jsc	Voc	FF	Eta
	[mA/cm²]	[mV]	[%]	[%]
Cz – 180 um	36.5	729	73.3	19.5



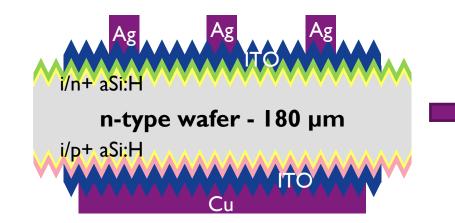
First freestanding cells made from epitaxial foils confirm the high electronic quality of the silicon foils



Туре	Jsc [m <b>A</b> /cm²]	Voc [mV]	FF [%]	Eta [%]
Cz – 180 um	36.5	729	73.3	19.5
Foil – 40 um	34.0	662	68.0	15.3
Foil – 40 um	34.7	715	40.4	10.0

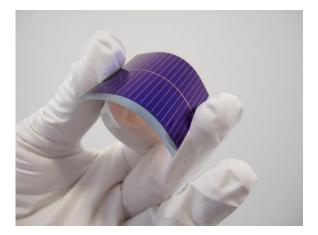
Cell area: 4 cm<sup>2</sup>

First freestanding cells made from epitaxial foils confirm the high electronic quality of the silicon foils





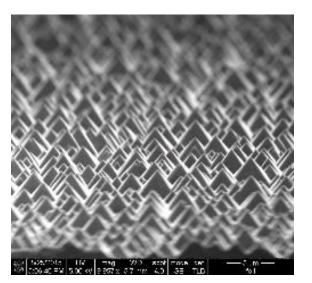
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Light in-coupling is very important for solar cells based on thin silicon foils

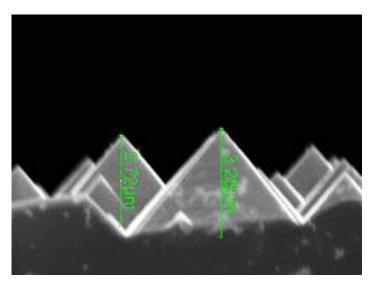


Random pyramid texturing of epitaxial silicon foils is possible

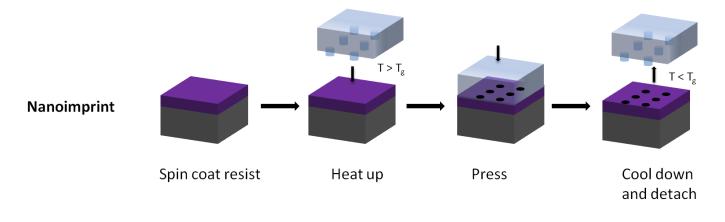


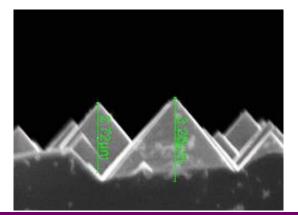
Surface texturing is mandatory to get good light in-coupling

However: 3-5 um of silicon gets etched on each side

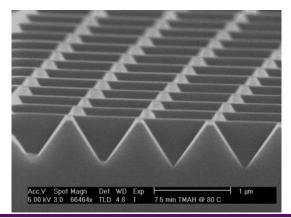


Inverted nano-pyramids made by nano-imprint lithography are an alternative to random pyramid texture leading to less silicon removal



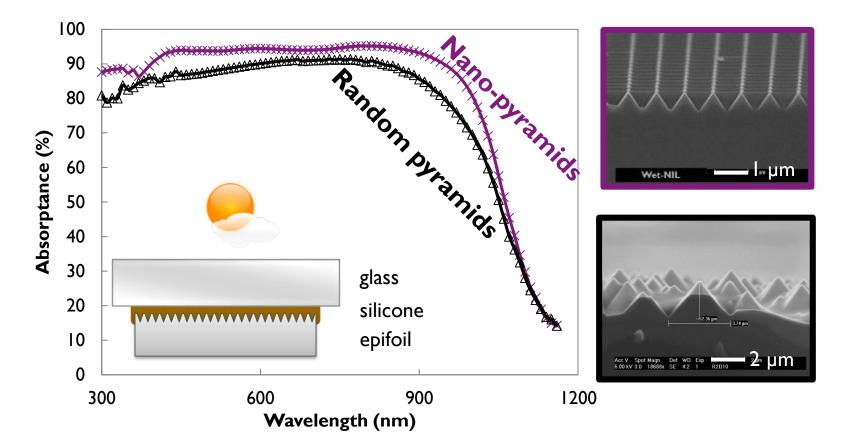


Random pyramids via KOH etching: 3-5 um Si removal



Inverted nano-pyramids by nano-imprint: 0.5 um Si removal

## Inverted nano-pyramids can optically outperform standard random pyramid texture



Experiment performed in collaboration with the company Obducat

Inverted nano-pyramids lead to higher Jsc values than random pyramids in freestanding cells made from thin foils



Inverted nanopyramids

Туре	Jsc [mA/cm²]	Voc [mV]	FF [%]	Eta [%]
Random pyramids	34.2	670	47.2	10.8
Inverted nano-pyramids	35.6	664	48.6	11.5

### CONCLUSIONS

#### **Conclusions**

- Porous-silicon based lift-off in combination with epiaxial silicon deposition can produce ultrathin silicon foils
- The resulting foils show minority carrier diffusion lengths which are 25 times as high as the foil thickness
- An SHJ-IBC cell process for silicon bonded to glass using silicones was developed leading to very high efficiencies and Voc values
- First cells with a simple cell structure were made from the epitaxial foils leading to efficiencies up to 15.3%
- Inverted nano-pyramids made by nano-imprint lithography can lead to higher Jsc values than random pyramids in cells made from epitaxial foils

#### **Acknowledgements**

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